ABSTRACT

LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

A porous member is used in a liquid removal system of an immersion lithographic projection apparatus to smooth uneven flows. A pressure differential across the porous member may be maintained at below the bubble point of the porous member so that a single-phase liquid flow is obtained. Alternatively, the porous member may be used to reduce unevenness in a two-phase flow.

[Figure 8]